

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	57829	(remov\$3 with (water liquid solvent impurities moisture)) with (substrate wafer)	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/08 09:24
L3	513	(remov\$3 with (water liquid solvent impurities moisture)) with (substrate wafer) with before with (coat\$3 deposit \$3)	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/08 09:24
L4	196	(remov\$3 with (water liquid solvent impurities moisture)) with (substrate wafer) with (before near2 (coat\$3 deposit \$4))	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/08 09:25
L5	151	(remov\$3 with (water liquid solvent impurities moisture)) with (substrate wafer) with (before near2 (coat\$3 deposit \$4))	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/08 09:28

L6	69	(remov\$3 near2 (water liquid solvent moisture)) with (substrate wafer) with (before near2 (coat\$3 deposit \$4))	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/08 09:29
S1	12	((vapor coat\$3 film) with deposit\$3) same (dehydrate with (substrate wafer))	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/08/12 12:29
S2	5791	((vapor coat\$3 film) with deposit\$3) same (drying with (substrate wafer layer))	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/08/15 11:13
S3	96	(coat\$3 deposit \$3) same (dehydrate with (substrate wafer))	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/07 16:27
S4	47	S3 and (silane silicon)	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/07 16:39
S5	12	((vapor coat\$3 film) with deposit\$3) same (dehydrate with (substrate wafer))	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/07 16:39
S6	5876	((vapor coat\$3 film) with deposit\$3) same (drying with (substrate wafer layer))	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2008/10/07 16:39

10/8/2008 10:10:47 AM

C:\Documents and Settings\Kstouffer\My Documents\EAST\Workspaces\10656840.
wsp